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(21)Application number : 08-010871 (71)Applicant : TOPPAN PRINTING CO LTD

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(54) POLYVINYL ALCOHOL-BASED COMPOSITION AND ITS PRODUCTION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain the subject composition excellent in resistance to water and moisture, and capable of preserving high gas barrier property inherent in polyvinyl alcohol-based resin even if exposed to a highly humid atmosphere.

SOLUTION: This composition is such a one that an inorganic lamellar compound such as montmorillonite is located at voids in a crosslinked polymer consisting of a modified polyvinyl alcohol-based resin. The inorganic lamellar compound particles can be surely located at the voids of the crosslinked polymer by dissolving the crosslinked polymer in a solvent followed by adding the inorganic lamellar compound in the resultant solution.

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